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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Application Serial No. .... 10/666,025  
Filing Date ..... September 17, 2003  
Inventor ..... Cem Basceri et al.  
Assignee ..... Micron Technology, Inc.  
Group Art Unit ..... 1762  
Examiner ..... Timothy Howard Meeks  
Attorney's Docket No. .... MI22-2407  
Title ..... Plasma Enhanced Chemical Vapor Deposition Method of Forming  
a Titanium Silicide Comprising Layer

**RESPONSE TO NOVEMBER 22, 2004 OFFICE ACTION**

To: Mail Stop Amendment  
Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

**VIA U.S. EXPRESS MAIL**

From: Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)  
Wells St. John P.S.  
601 West First Avenue, Suite 1300  
Spokane, WA 99201-3828

Responsive to the Office Action dated November 22, 2004, Applicant  
amends and remarks as follows:

**AMENDMENTS**

02/22/2005 MWOLGE1 00000024 10666025

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